



prep*FAST* PPQ

Automated Sample Preparation and Introduction System for PPQ Metals Determination in High Purity Chemicals

The prepFAST PPQ is the most advanced tool for analyzing ultrapure semiconductor grade chemicals with ICPMS detection. The prepFAST PPQ utilizes syringe-driven flows of UPW, semiconductor grade acids, and standard solution to automate both sample dilutions and standard curve generation. It eliminates manual handling of samples to deliver sub-ppq detection limit capabilities in concentration mode and sub-ppt detection limit capabilities in direct analysis mode.

Two High Purity Modes

Direct Analysis Mode

- Capability to analyze all semiconductor grade chemicals
- Sub-PPT detection limits for all semiconductor elements
- General purpose for any sample matrix
- Automated MSA calibration
- Automated inline dilution

Concentration Mode

- Suitable for UPW, 30% $\rm H_2O_2$, and IPA
- Sub-PPQ detection limits
- Removes difficult matrices such as IPA while recovering metals
- Removes impact of ICPMS interferences and backgrounds on results
- Amplified sensitivity compared to direct analysis
- Automated MSA calibration

prepFAST PPQ Autocalibration

The prep*FAST* PPQ automatically prepares calibration curves for over 40 elements controlled in semiconductor manufacturing processes. Calibrations are generated by automatically diluting an enclosed multielement stock standard. Automation with the high-purity prep*FAST* PPQ achieves low to sub-ppt calibrations in direct analysis mode and low ppq calibrations in concentration mode.



prep*FAST* PPQ System

High Purity Automation with PPT/PPQ results

Automation

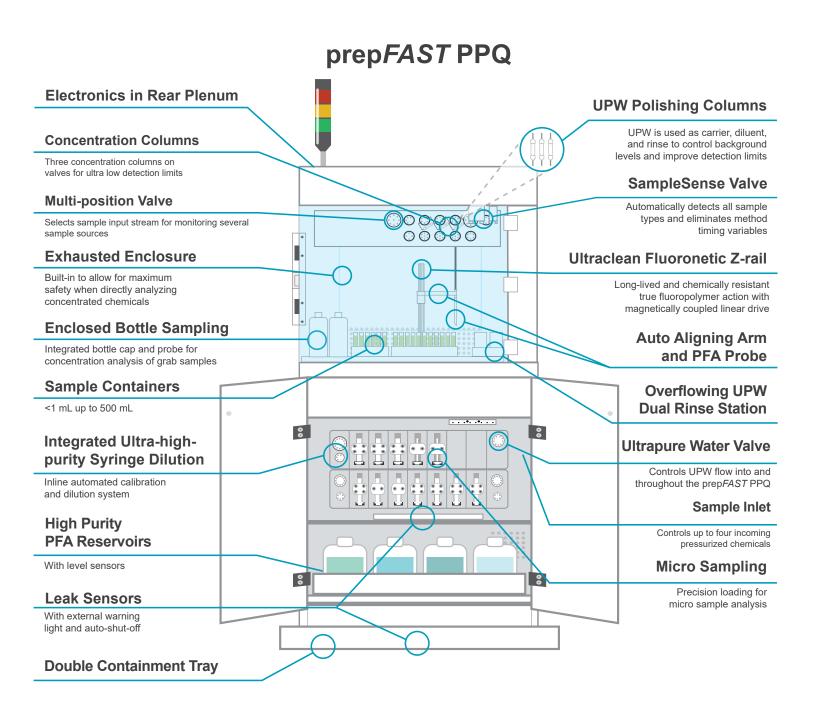
- Automatic external and MSA calibrations
- Automated sample sensing
 - Accounts for viscosity and automatically adjusts timing
 - Detects and injects the sample and triggers the ICPMS
- Automated syringe-driven sample introduction
 - Sample loading
 - Sample preparation
 - Inline dilution
 - Acid addition (direct mode only)

Ultraclean

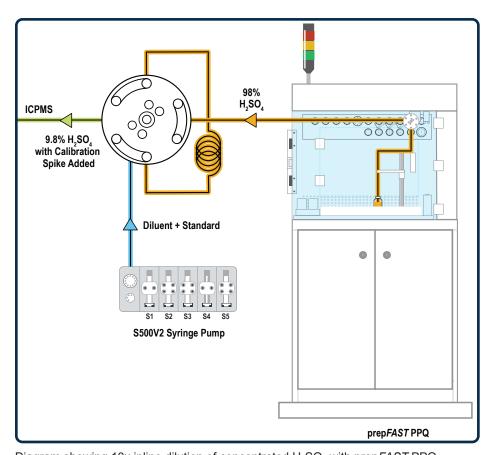
- Ultraclean sample preparation
- Integrated ultraclean sample environment
 - Includes ultraclean air shower
 - Sample racks for PFA containers (<1 mL to 500 mL)
- Continuously-flowing high purity UPW rinse (user-supplied UPW)
- UPW polishing columns for low background

| prep <i>FAST</i> PPQ System | | | | | | |
|-----------------------------|---|--------------------------|-------------------------------------|---|----------------------|---------------------------|
| System | Integrated Mobile Autosampler & Enclosure | Ultraclean Air Shower | Integrated FAST valve modules | PFA Nebulizer with Integrated Capillary | PFA Sample Probes | Syringe Pump S500V2 |
| prep <i>FAST</i> PPQ | √ | \checkmark | √ | √ | \checkmark | \checkmark |

Pure Automation



prepFAST PPQ Inline Dilution of Semiconductor-grade Chemicals



The prepFAST PPQ allows dilution by volume or weight for IPA and H₂O₂ in concentration mode, and all semiconductorgrade chemicals in direct analysis mode. Metals are quantified using automated inline MSA or external calibration. Automated direct analysis of concentrated chemicals eliminates sample contamination caused by manual dilution into a secondary container.

Diagram showing 10x inline dilution of concentrated H₂SO₄ with prepFAST PPQ.

| Examples | of Semicono | luctor Chemica | ls Analyzed | at the ppt | Level with pr | ep <i>FAST</i> PPQ* |
|----------|------------------------------------|------------------------------------|----------------------|------------|---------------|-----------------------------------|
| Acids | 98% H ₂ SO ₄ | 89% H ₃ PO ₄ | 70% HNO ₃ | 49% HF | 35% HCI | 30% H ₂ O ₂ |
| Bases | 22% NH ₄ OH | 2.38% TMAH | 25%TMAH | KOH | | |
| Organics | IPA | PGMEA/PGME | Photoresist | NMP | Butyl Acetate | Cyclohexanone |

^{*}This table contains only a partial list of chemicals which can be analyzed using prepFAST PPQ in direct analysis mode.

Concentration Mode

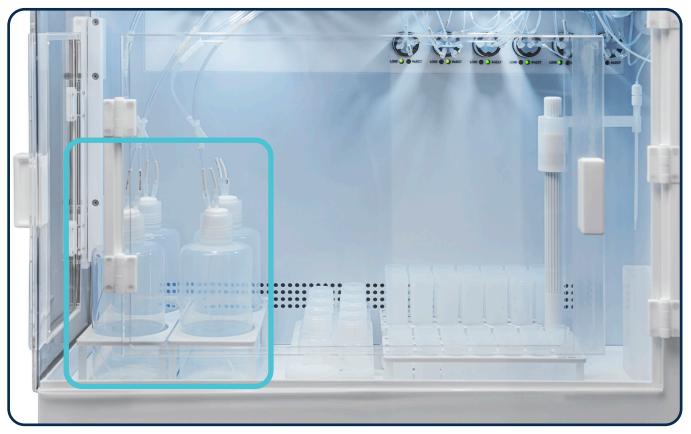
Sampling Options in Concentration Mode

Direct sample modules

- Availability to monitor up to four pressurized sample lines
- Flushing and sampling processes are controlled by an all-fluoropolymer valve manifold

Enclosed bottle samples

- Rack with integrated probes and caps to keep bottled samples fully enclosed before and during sampling
- Can accomodate up to 2L bottles
- Automated UPW probe rinse between samples



Layout of four 1L enclosed bottle samples to the left of the autosampler.

Example of Detection Limits in Non-cleanroom Environment in Concentration Mode (1000x Concentration Factor)

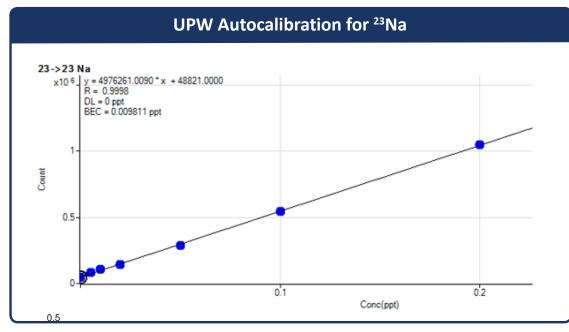
| in concentration mode (1000x concentration 1 actor) | | | | | | |
|---|----------|--------------------------|----------|--|--|--|
| Element | DL (PPQ) | Element | DL (PPQ) | | | |
| ⁷ Li | 0.02 | ⁸⁵ Rb | 0.01 | | | |
| ¹¹ B | 9 | ⁸⁸ Sr | 0.06 | | | |
| ²³ Na | 0.6 | ⁹⁰ Zr | 0.1 | | | |
| ²⁴ Mg | 0.2 | ⁹³ Nb | 0.2 | | | |
| ²⁷ AI | 0.6 | ⁹⁸ Mo | 0.3 | | | |
| ²⁸ Si | 240 | ⁷⁵ As | 0.2 | | | |
| ³⁹ K | 0.4 | ¹⁰⁷ Ag | 0.05 | | | |
| ⁴⁰ Ca | 0.3 | ¹¹⁴ Cd | 0.06 | | | |
| ⁴² P | 2 | ¹¹⁵ ln | 0.01 | | | |
| ⁴⁸ Ti | 0.2 | ¹¹⁸ Sn | 0.5 | | | |
| ⁵¹ V | 0.7 | ¹²¹ Sb | 0.4 | | | |
| ⁵² Cr | 0.4 | ¹³³ Cs | 0.007 | | | |
| ⁵⁵ Mn | 0.07 | ¹³⁸ Ba | 0.04 | | | |
| ⁵⁶ Fe | 0.3 | ¹⁸⁰ Hf | 0.2 | | | |
| ⁵⁸ Ni | 0.07 | ¹⁸¹ Ta | 0.3 | | | |
| ⁵⁹ Co | 0.01 | 184 W | 0.4 | | | |
| ⁶³ Cu | 0.07 | ¹⁹⁵ Pt | 0.1 | | | |
| ⁶⁴ Zn | 0.4 | ²⁰⁵ TI | 0.03 | | | |
| ⁶⁹ Ga | 0.004 | ²⁰⁸ Pb | 0.05 | | | |
| ⁷⁴ Ge | 0.6 | ¹⁰⁶ Pd | 0.4 | | | |
| | | | | | | |

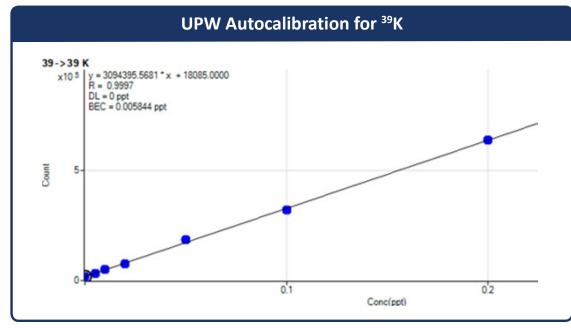
Concentration Mode

prepFAST PPQ Autocalibration

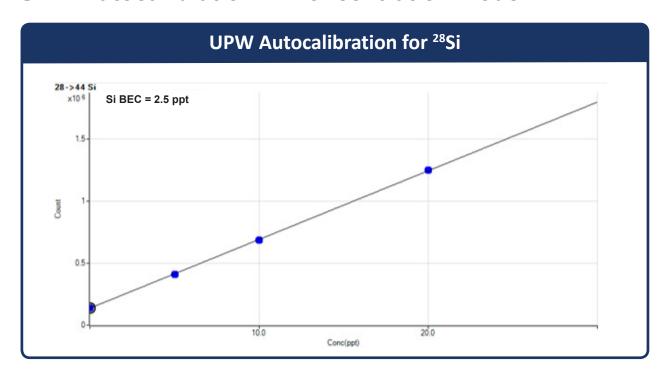
Autocalibrations for elements controlled in semiconductor manufacturing processes are generated by automatically diluting an enclosed multielement stock standard. Automation with the high-purity prep*FAST* PPQ achieves ppt to sub-ppt calibration in direct analysis mode and ppq calibrations in concentration mode.

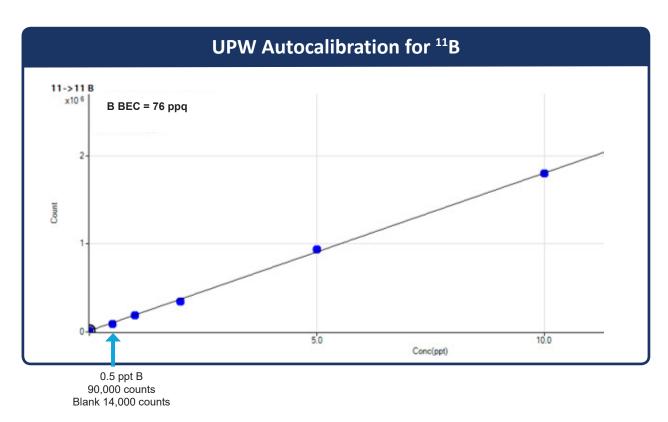
UPW Autocalibration in Concentration Mode





UPW Autocalibration in Concentration Mode



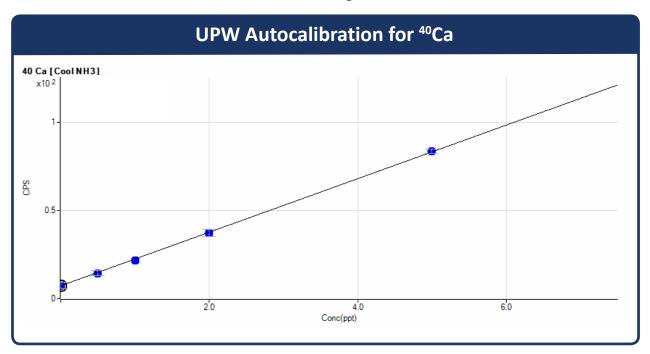


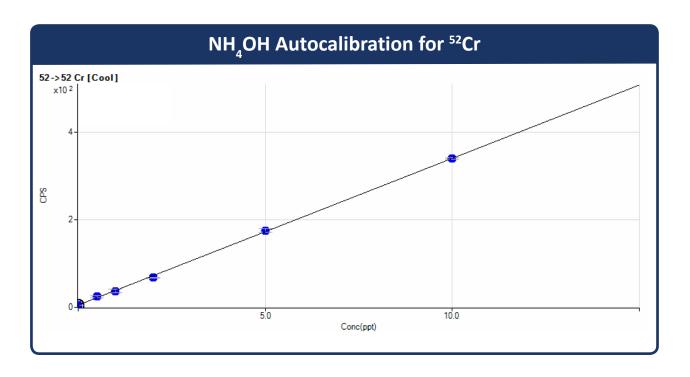
Direct Analysis Mode

Direct Analysis Mode

| Example of Detection Limits in Non-cleanroom Environment in Direct Analysis Mode | | | | | |
|--|----------|--------------------------|----------|--|--|
| Element | DL (ppt) | Element | DL (ppt) | | |
| ⁷ Li | 0.02 | ⁷² Ge | 0.04 | | |
| ⁹ Be | 0.007 | ⁷⁵ As | 0.2 | | |
| ¹¹ B | 0.9 | ⁸⁵ Rb | 0.008 | | |
| ²³ Na | 0.07 | ⁸⁸ Sr | 0.008 | | |
| ²⁴ Mg | 0.01 | ⁹⁰ Zr | 0.004 | | |
| ²⁷ A I | 0.03 | ⁹³ Nb | 0.002 | | |
| ^{39}K | 0.06 | ⁹⁵ Mo | 0.5 | | |
| ⁴⁰ Ca | 0.4 | ¹¹¹ Cd | 0.07 | | |
| ⁴⁸ Ti | 0.02 | ¹¹⁵ In | 0.004 | | |
| ⁵¹ V | 0.1 | ¹¹⁸ Sn | 0.05 | | |
| ⁵² Cr | 0.1 | ¹²¹ Sb | 0.05 | | |
| ⁵⁵ Mn | 0.009 | ¹³⁷ Ba | 0.04 | | |
| ⁵⁶ Fe | 0.04 | ¹⁷⁸ Hf | 0.003 | | |
| ⁵⁸ Ni | 0.01 | ¹⁸¹ Ta | 0.01 | | |
| ⁵⁹ Co | 0.007 | ¹⁸² W | 0.01 | | |
| ⁶⁰ Ni | 0.01 | ²⁰⁵ TI | 0.002 | | |
| ⁶³ Cu | 0.03 | ²⁰⁸ Pb | 0.005 | | |
| ⁶⁴ Zn | 0.04 | ²³² Th | 0.000 | | |
| ⁷¹ Ga | 0.002 | 238⋃ | 0.003 | | |

Autocalibration in Direct Analysis Mode











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